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LEE0023-US

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

SHIH-CHANG CHANG ET AL.

Serial No.: 10/690,703

Filed: OCTOBER 23, 2003

For: SEMICONDUCTOR DEVICE WITH  
LIGHTLY DOPED DRAIN AND  
METHOD OF MANUFACTURING  
THE SAME

Art Unit: 2814

Examiner: PERALTA, GINETTE

**AMENDMENT AND RESPONSE TO RESTRICTION REQUIREMENT**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In response to the Office Action mailed on June 29, 2005, please amend the above-identified application as follows:

No extension of time or other fees are believed to be due, except as detailed in the attached documents. However, any extension of time necessary to prevent abandonment is hereby requested, and any fee necessary for consideration of this response is hereby authorized to be charged to Deposit Account Number 50-1390.

**Amendments to the Specification:** None.

**Amendments to the Claims:** reflected in the listing of claims that begins on page 2 of this paper.

**Remarks:** begin on page 8 of this paper.